Laser cutter ONPY-LC1

Extended resources for Failure Analysis (FA) in ONPY

Subject:

This document outlines analytical possibilities of the laser cutter system in OPNY2

Content:

This system was completed in ONPY for electrical failure analysis. Components from various suppliers were used.

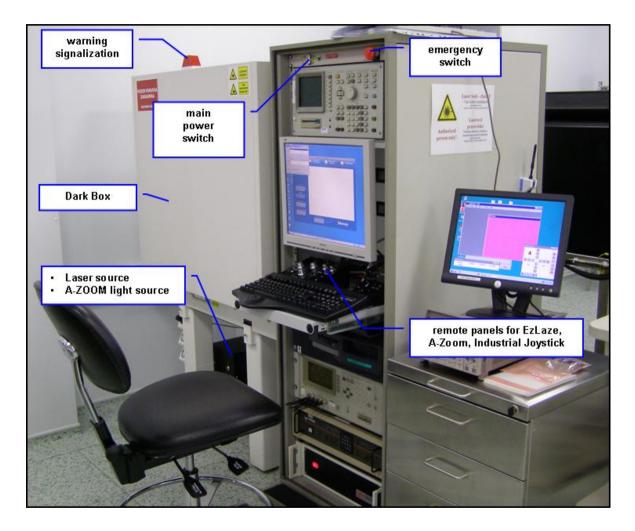
Reference documents

12MON23542D, 12MON22866D



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Laser cutter (outline)



Detailed information can be found in 12MON23542D

Laser EzLaze II:

wavelengths: 355 nm (NUV) 533 nm (Green) Attenuator setting: 0-999 Pulse continual: 1 Hz

Optical system:

A-ZOMM microscope polarizer/analyzer filters Magnifications: 20-1500 Objectives:

2x (Aperture=0.055, WD= 34 mm) 20x (Aperture=0.42, WD= 20 mm) 50x NUV * (0.42, WD= 20.5 mm) 100x NUV * (0.5, WD= 13 mm) (* appropriate for laser cutting)

Prober Wentworth MP-2010

Motorized X-Y-Z stage
Resolution 0.1 um
8" thermo chuck (gold plated)
Theta adjustment +/- 15°

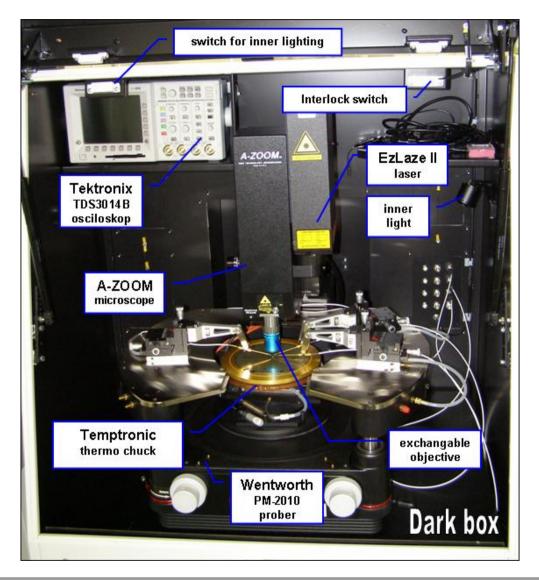
Instrumentation:

HP 4145B semiconductor analyzer HP4284A RLC meter Temptronics TPO3010B thermocont. Tektronix TDS3014B oscilloscope Fluke 189 handheld multimeter Fluke 62 mini IR thermometer



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Dark box



<u>Dark box</u>

- EMC isolation
- Optical isolation
- Interlock Switch for safety operation
- Warning signalization

Connector panel with BNC

- 4 x SMU (100 mA max, HP41455B)
- 2 x VMU (Voltage Monitor Units)
- 2 x VSU (Voltage Source Units)
- 2 x RLC meter (HP4284A)
- 1 x Interlock connector
- 1 x 12V light power source connector

Tektronix TDS3014B

- 4-channel digital storage oscilloscope
- 100 MHz, TCP-IP, GP-IB
- 4 x voltage probe
- 1 x current probe (up to 15A)

Prober

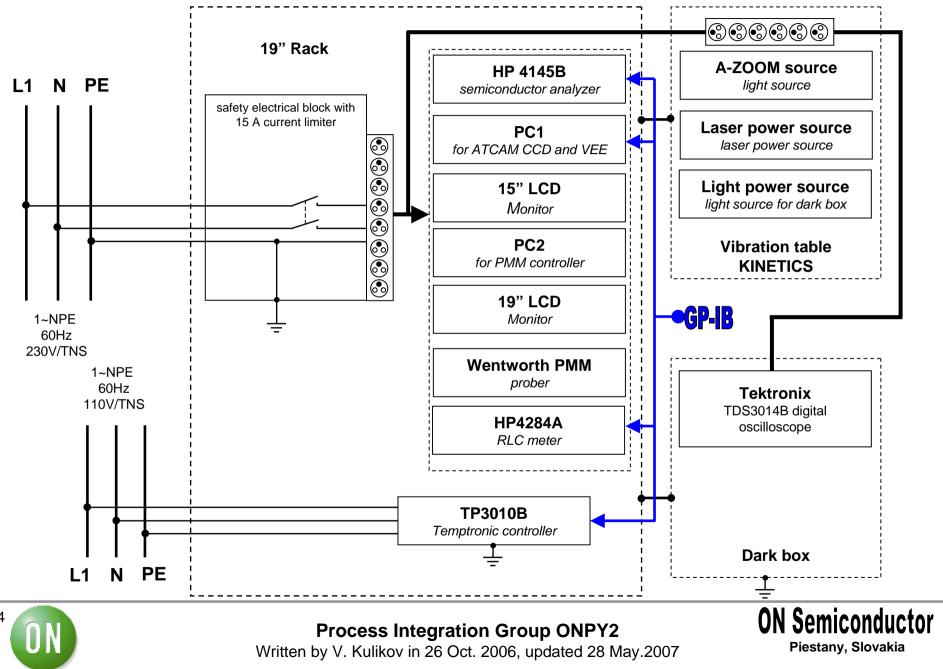
- 4 x precise vacuum micromanipulators determined for micro-probing
- available probe needles with tip diameter 0.25 um and 0.1 um
- available probe needles with 1 um (contact pads)



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Electrical installation schematic



Laser cutter system resources

Laser cutting

- cutting SiO2, SiN, AI, SOG, Poly Si, etc.
- minimum cut size 1 x 1 um (using objective 100X)
- maximum cut size 50 x 50 um (using 50X objective)

Thermal liquid crystal analysis

-hot spot analysis available liquid crystals LC1: NP4, clearing temperature: 76°C LC2: ME6N, clearing temperature: 47.5°C LC3: ME105, clearing temperature: 42,9°C LC4: BN/R42C1W, clearing temperature: 53,3°C LC5: K18 (MERK), clearing temperature: 29°C

DC characterization

available:

- 4 x SMU, 2 x VMU, 2 x VSU
- 5 x micro-manipulators + Probe card holder
- applicable temperature range from 10°C 125 °C (see page 7)
- micro-probing

Impedance characterization

- characterization of capacitors, Rs, Rp, G, L, etc.
- applicable temperature range from 10°C 125 °C
- micro-probing

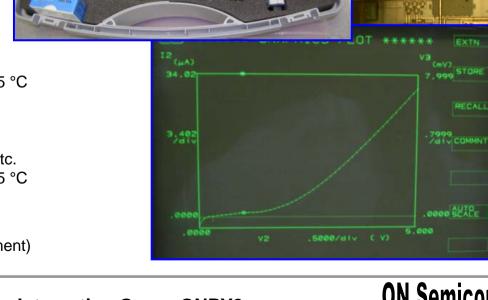
Automation of measurement

- Agilent VEE 7.5 (Visual Engineering Environment)
- GP-IB, TCP-IP communication



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cut



laser cutting with on-line IV monitoring by using probe card with holder

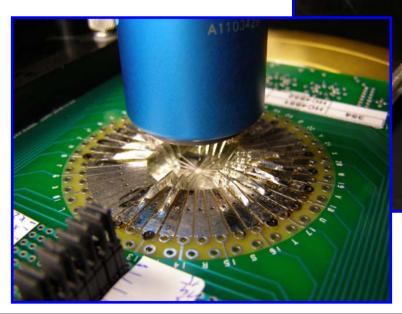
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Probe card format:

- Electroglas compatible

Available activities in parallel during probing with probe card :

- Laser cutting (due to large working distance of objectives)
- Additional micro-probing
- Liquid crystal analysis
- Thermal conditioning

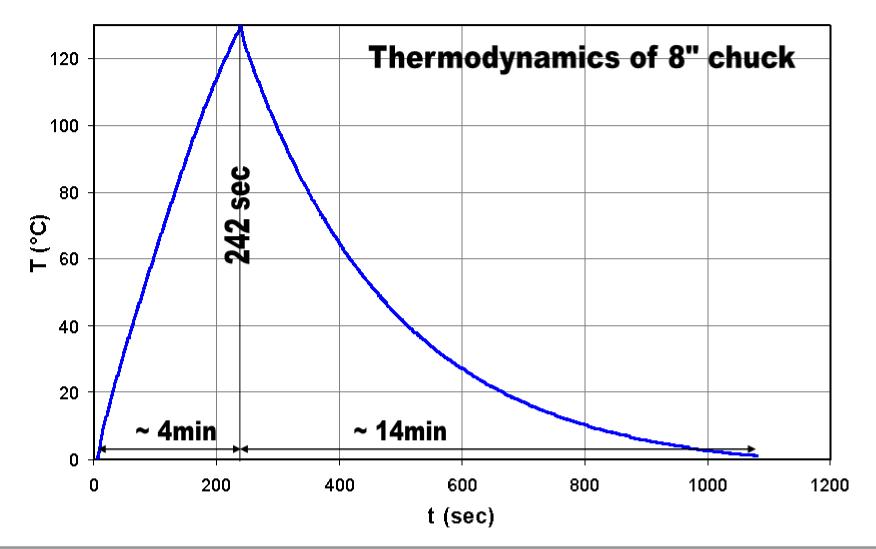




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Thermo-chuck characterization (measured involving Agilent VEE7.5)

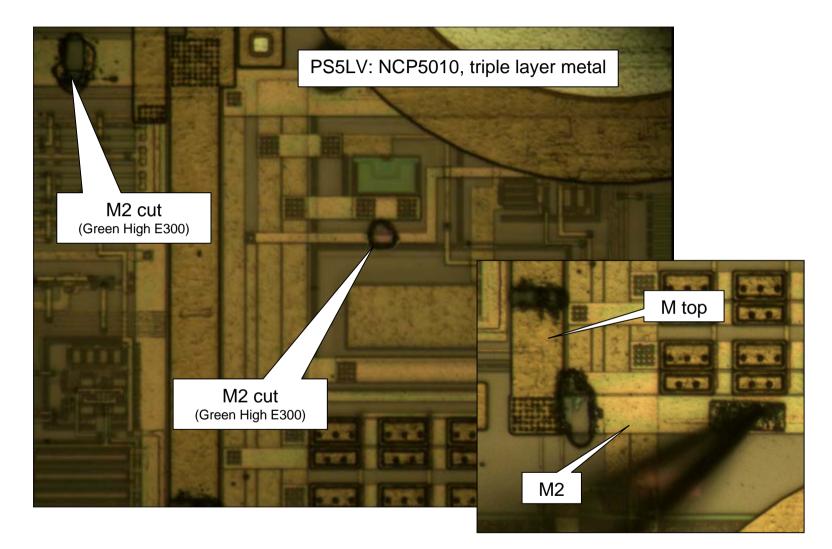




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Example of Laser cutting (Metal2 through SiN-ILD2-SOG-ILD1-AICu0.5 6000A)



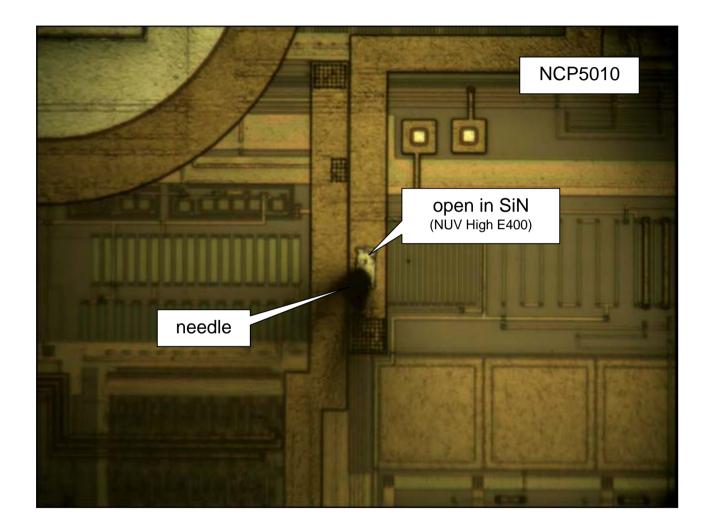


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Example of Micro-probing (to Metal top with opened window in passivation layer)

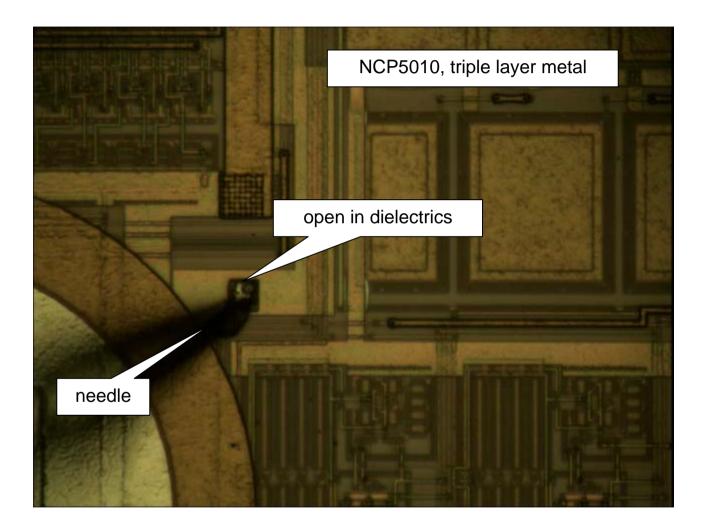




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Example of Micro-probing (to Metal2 top with opened window in dielectric layers SiN-ILD2-SOG-ILD1)





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